

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application No.	09/855,321
	Filing Date	May 14, 2001
	First Named Inventor	Suntola et al.
	Art Unit	1762
(Multiple sheets used when necessary)	Examiner	David Turocy
SHEET 1 OF 1	Attorney Docket No.	ASMMC.013C2

NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
DT	1	Lei et al., "Real-time observation and optimization of tungsten atomic layer deposition process cycle", American Vacuum Society, 2006, pages 780-789	
DT	2	Ritala et al., "Atomic Layer Deposition", Handbook of Thin Film Materials, 2002, pages 103-159, Vol. 1	

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Examiner Signature	/David Turocy/	Date Considered	02/07/2007
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			

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